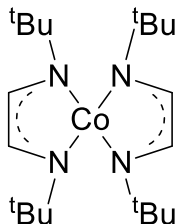


Catalog # 27-1025 Bis(1,4-di-t-butyl-1,3-diazabutadienyl)cobalt(II) Co(DAD)₂, min. 98% (99.999%-Co)
PURATREM



Thermal Behavior:

- TGA available in [1, 3].
- Sublimation at 115 °C / 0.05 Torr [1, 3], 100 °C / 0.75 mTorr [3].
- Melting point 174-175 °C [1, 3].
- Solid state decomposition temperature 235 °C [1].

Technical Notes:

1. Volatile and thermally stable precursor for the growth of Co containing thin films by ALD and CVD. The high reactivity of the precursor enables the growth of pure Co metal films at low temperatures with various reducing agents.

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Co	ALD	127-130 °C	5-9 Torr	HCOOH	140-240 °C	[2, 5]
Co	ALD	130 °C	6-9 Torr	^t BuNH ₂ , Et ₂ NH	160-220 °C	[4, 6, 7]
Co	ALD	150 °C		HCOOH, ^t BuNH ₂	180 °C	[8]
Co ₃ O ₄	ALD	95-100 °C	4 Torr	O ₃	100-150 °C	[3]

References:

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8. [Appl. Surf. Sci. 2020, 510, 144804.](#)